

**INFORMATION DISCLOSURE  
CITATION IN AN  
APPLICATION  
(PTO-1449)**

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APPLICANT  
SHANMUGASUNDRAM et al.

**FILING DATE**  
August 31, 2001

GROUP  
2823

## U.S. PATENT DOCUMENTS

[illegible]

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**EXAMINER**

DATE CONSIDERED

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

<p align="center"><b>INFORMATION DISCLOSURE CITATION IN AN APPLICATION</b></p> <p align="center">(PTO-1449)</p>	<p>ATTY. DOCKET NO. 005920 USA/MTCG/PCTRL/JW</p>	<p>SERIAL NO. 09/943,383</p>
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<p>(a)</p>	<p>January 24, 2005. International Preliminary Examination Report from PCT Application No. PCT/US02/19117.</p>	
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